

CONTENTS

A Study on the Surface Modification of LDPE by Low-Temperature Plasma	1
Hu Jianfang, Xia Meiqun, Guo Shujin, Li Heli, Guo Ying, Chen Siqin and Hong Mingyuan, China	
Plasma Graft Polymerization of Hydrophilic Monomers	9
Toshihiro Hirotsu, Japan	
The Structure and Properties of the Copolymer of Vinyltrimethylsilane with Benzene, Styrene, and Hexafluoropropylene	23
Wenge Yan, Jie Chen and Lizhen Lu, People's Republic of China	
The Synthesis of Polyacetylene-Type Polymers under Dense-Medium Plasma Conditions	35
C. I. Simionescu, F. Denes, S. Manolache and C. Badea, Romania	
Fluorination of Polymeric Films by a Nonequilibrium Plasma at Low and Atmospheric Pressures: Evolutions of Wettability and Adhesive Properties	49
S. Mournet, F. Arefi, P. Montazer-Rahmati, M. Goldman and J. Amouroux, France	
Formation of Semiconductive Thin Films on Different Substrates by Glow Discharge Polymerization of Organometallic Compounds	67
F. Tchoubineh, S. Mondin, F. Arefi and J. Amouroux, France	
The Use of Reactive Facet Tapering for Multilevel Interconnect Applications in Semiconductor Device Fabrication	69
T. Abraham and I. Wylie, Canada	

Adhesion of Thin Hard Carbon Films	89
Stanislaw Mitura and Zdzislaw Has, Poland	
The Surface of Carbon Fibers Continuously Treated by Cold Plasma	99
Sun Mujin, Hu Baorong and Da Youxian, People's Republic of China	
Flowless Systems in Plasma Chemical Kinetics	113
V. I. Zyn, U.S.S.R.	
Energy Spectrum of Ions Produced in the Cathode Fall of Ion Sources	143
Z. Wronski, Poland	
Growth Mechanism and Morphology of Boron Films in Plasma-Enhanced Chemical Vapor Deposition from B₂H₆ + He (+ H₂)	149
Shojiro Komatsu and Yusuke Moriyoshi, Japan	
Effects of Distance from Sputtering Source to Sample on Ion-Plated Al Films	195
L. J. Wan and K. H. Kuo, People's Republic of China	
Preparation of Plasma Polymer Metal Composite Films and Their Electrical and Optical Properties	205
A. Heilmann, G. Kampfrath and C. Hamann, Germany	
Formation and Structure of Composite Layers Produced on Steels by Plasma Thermochemical Treatment	227
T. Wierzchon, J. Michalski and T. Karpinski, Poland	
TEM Study of Cross-Sectional Characterizations of Ion-Plated TiN and (Ti, Al)N Films	237
Lijun Wan, People's Republic of China	
Diffusion Barrier Properties of Sputter-Deposited WTi and TiN Thin Films	245
M. Milosavljević, N. Bibić, J. Turković, M. Stojanović, and D. Perusko, Yugoslavia	
I. H. Wilson, United Kingdom	
Application of Microwave Plasmatrons in Chemistry and Technology	267
R. Parosa and E. Reszke, Poland	